

PATENT
8017-1194

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Katsumi MAEDA et al.

Conf.

Application No. **NEW NATIONAL PHASE**

Group

Filed August 25, 2006

Examiner

STYRENE DERIVATIVE, STYRENE POLYMER, PHOTSENSITIVE RESIN
COMPOSITION, AND METHOD FOR FORMING PATTERN

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

August 25, 2006

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

Amendments to the Claims are reflected in the listing of claims which begin on page 2 of this paper.

Remarks begin on page 6 of this paper.